HANDLING PLATFORM
FOR 450 MM WAFERS

APPLICATIONS

- Wafer handling studies
- Robot assessment
- End effector assessment
- Equipment assessment
- Equipment development

What is your application?

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R&D AND ASSESSMENT FOR
450 MM EQUIPMENT

The 450 mm cluster platform at Fraunhofer IISB provides a unique opportunity for equipment suppliers to assess and/or develop 450 mm semiconductor equipment without having to concern themselves with automation and wafer handling.

You are preparing demonstrator equipment for 450 mm processing or metrology? You are about to take a first step into 450 mm modules? You develop components or OEM parts for 450 mm equipment?

We offer you a playground and substantial support for 450 mm research, development, test, and assessment in our industry-compliant environment.

Fraunhofer IISB 450 mm R&D cluster platform – your opportunity to bring your core competence to market

SPECIFICATIONS OF THE CLUSTER PLATFORM

- 450 mm and 300 mm wafer handling without retrofitting
- Pressure range from atmospheric to high vacuum ($10^{-7}$ Torr)
- Transport Max Reach (TMR) of the central robot: 545 mm
- Wafer Transfer Plane (WTP) is variable between 1100 mm and 1400 mm
- Vacuum alignment tunnel and cooling station integrated
- Versatile metrology module to evaluate metrology components (in development)

DEVELOPMENT SUPPORT AT FRAUNHOFER IISB

Fraunhofer IISB has outstanding experience in the field of semiconductor equipment development and assessment.

Fraunhofer IISB supports you with:

- Cleanroom facilities up to class 10
- Various capabilities for measurement and characterization
- Accredited analysis laboratory for micro and nanotechnology
- Possibility of resizing 450 mm wafers to 300 mm or below in order to fit measurement equipment or subsequent process equipment